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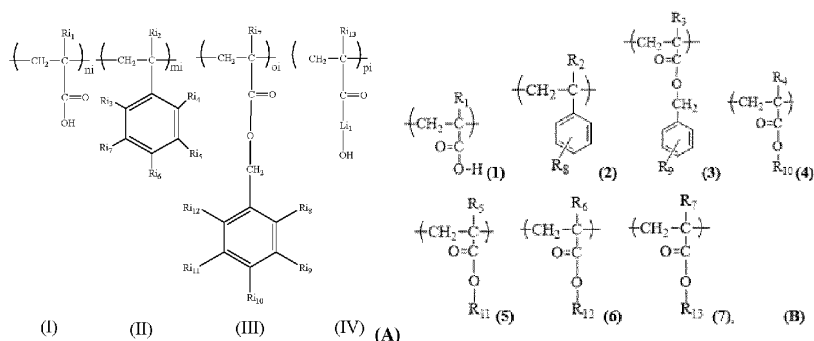
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(54) Title: POSITIVE TONE ULTRA THICK PHOTORESIST COMPOSITION



(57) Abstract: A positive working chemically amplified photosensitive composition comprising: Component a) at least one random copolymer, having structure (A), component b) at least one acrylic polymer component of structure (B) comprising repeat units selected from ones having structure (1), (2), (3), (4), (5), (6), and (7); component c) at least one Novolak polymer; component d) at least one photoacid generator (PAG); component e) at least one base additive; component f) at least one heterocyclic thiol compound; and component g) an organic spin casting solvent.

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